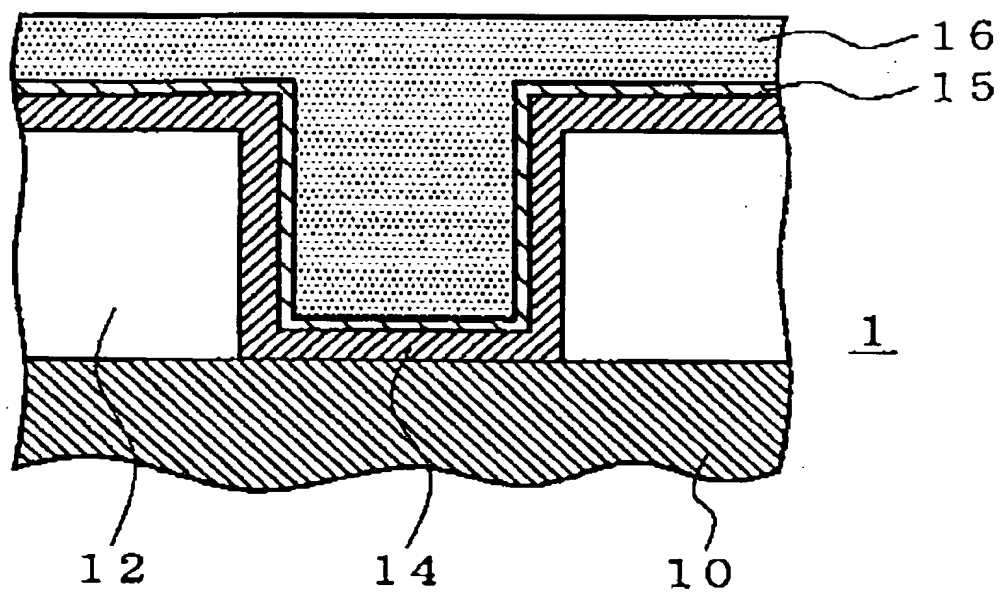
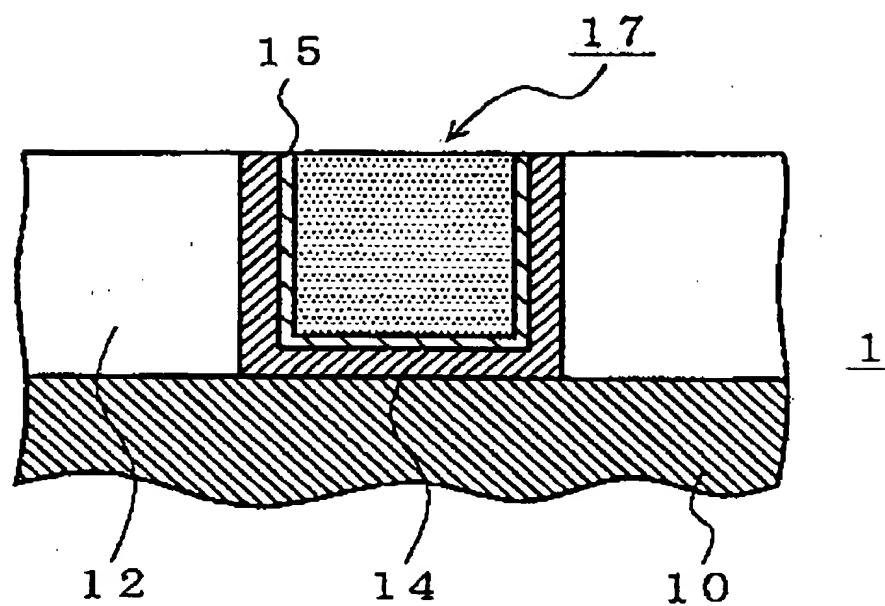


FIG. 1A prior art



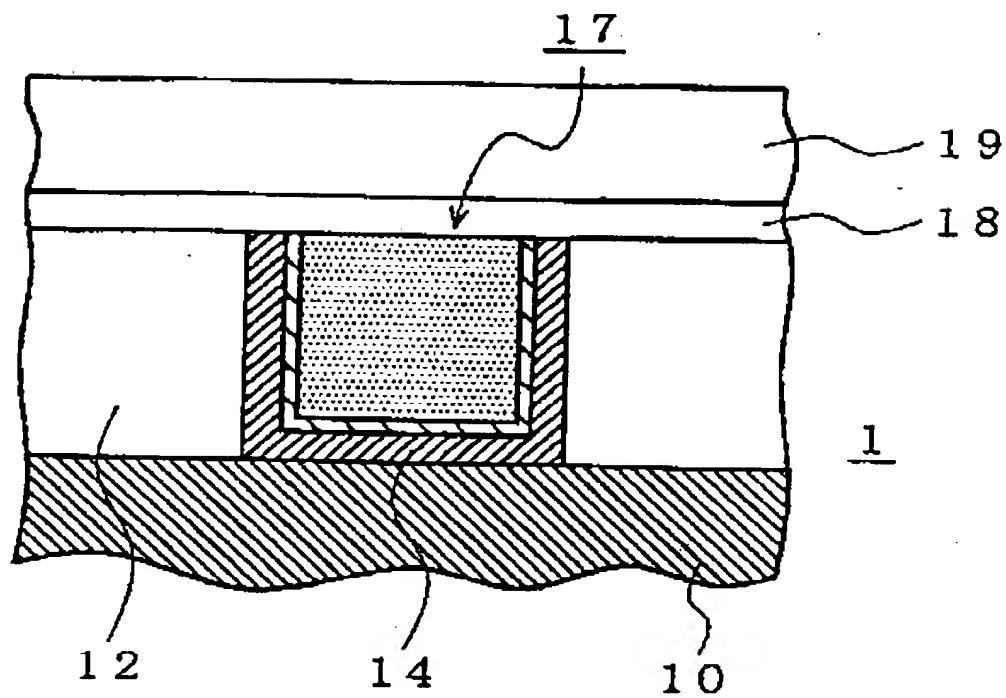
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FIG. 1B prior art



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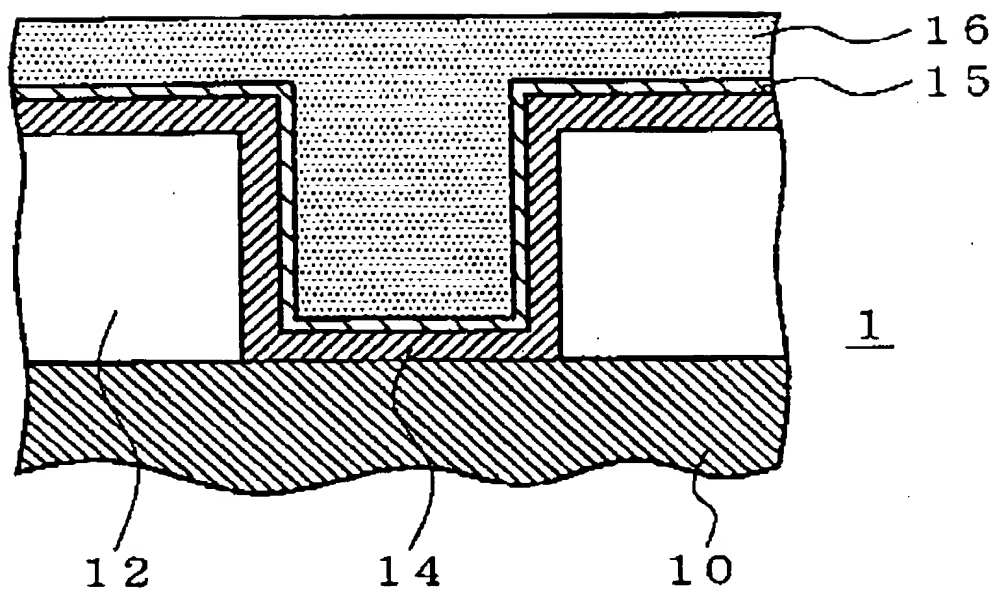
FIG. 1C prior art



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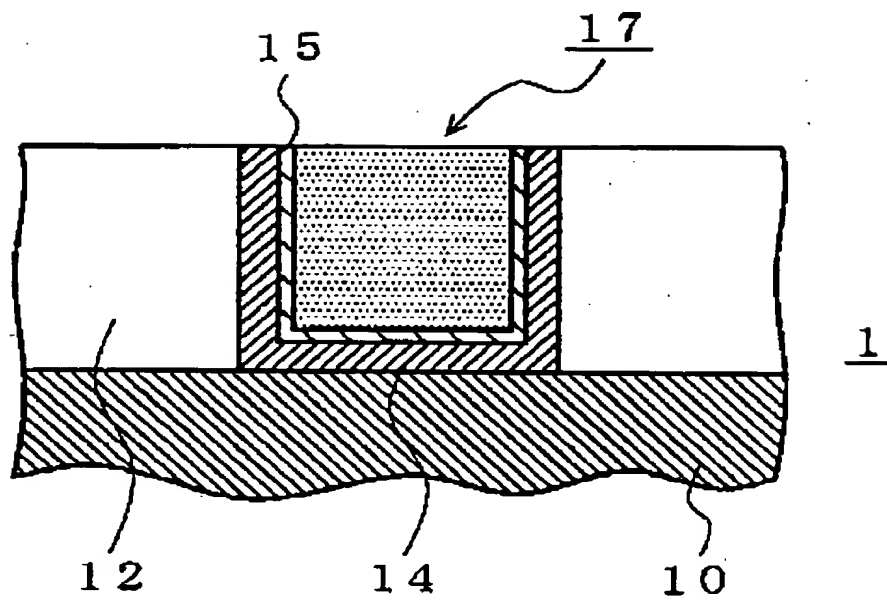
FIG. 2A



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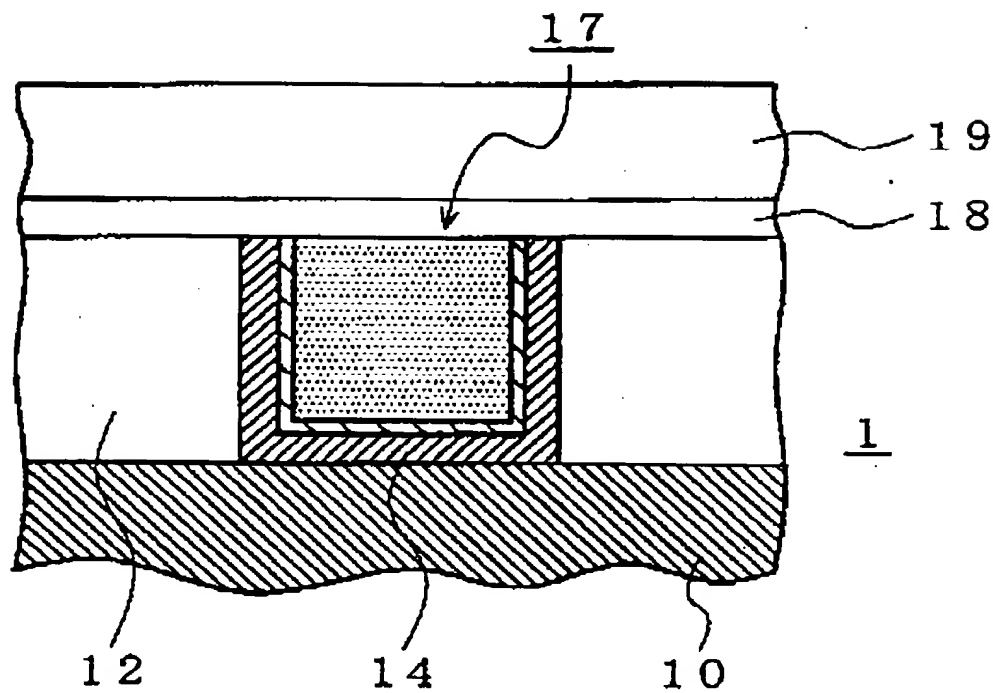
FIG. 2B



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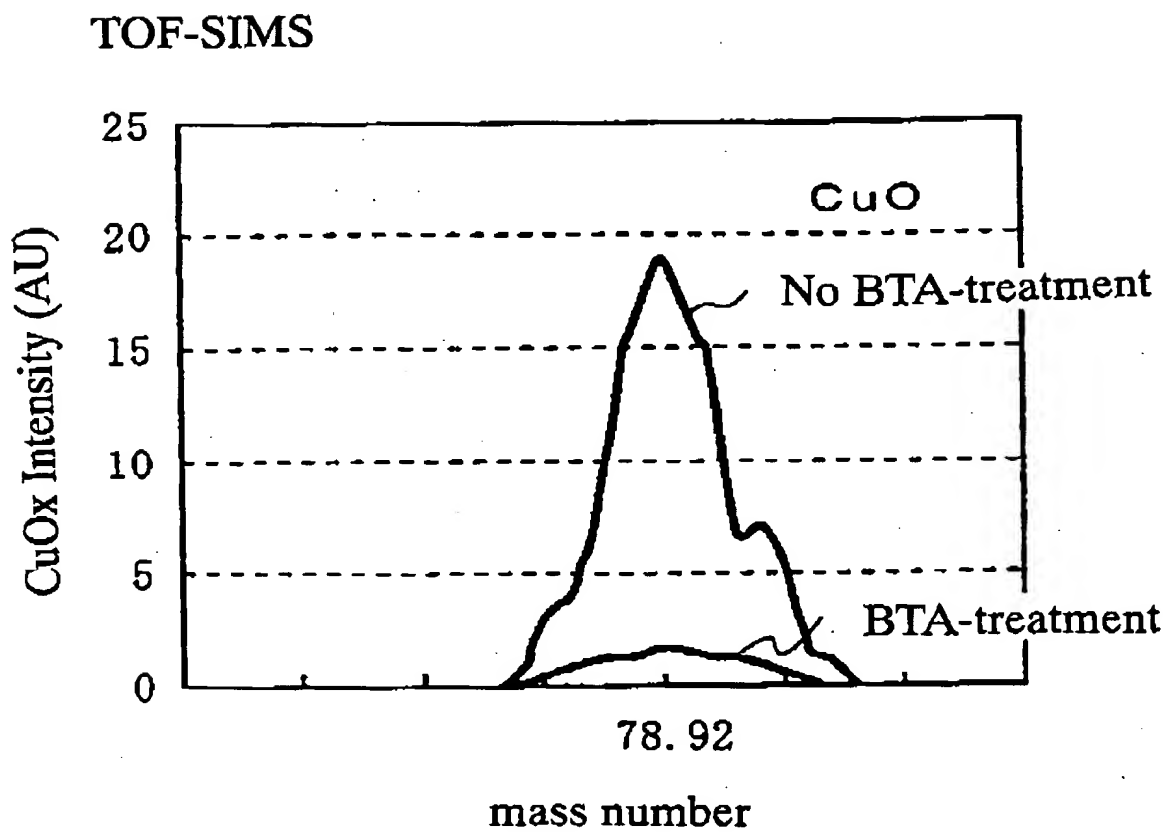
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FIG. 2C



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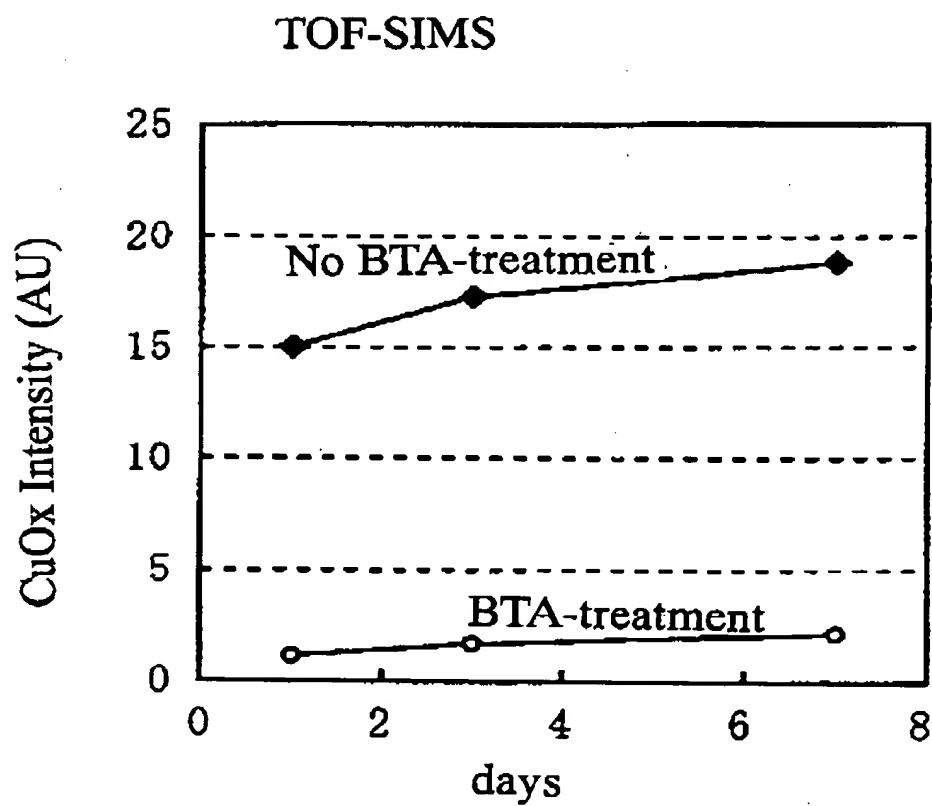
FIG. 3A



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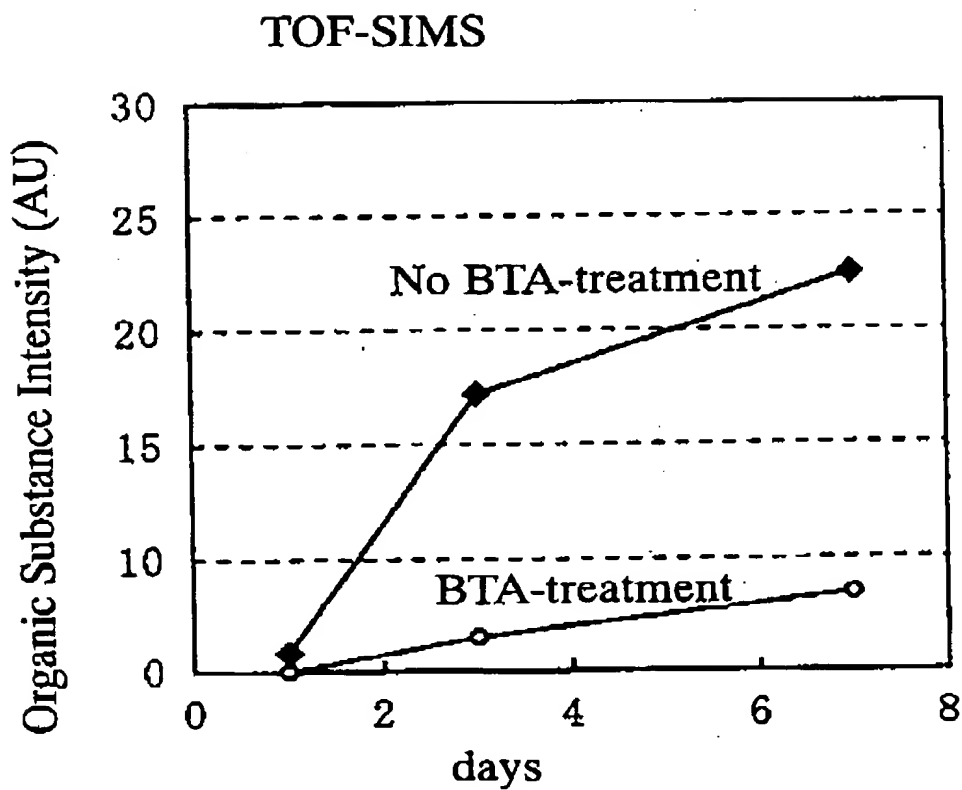
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FIG. 3B



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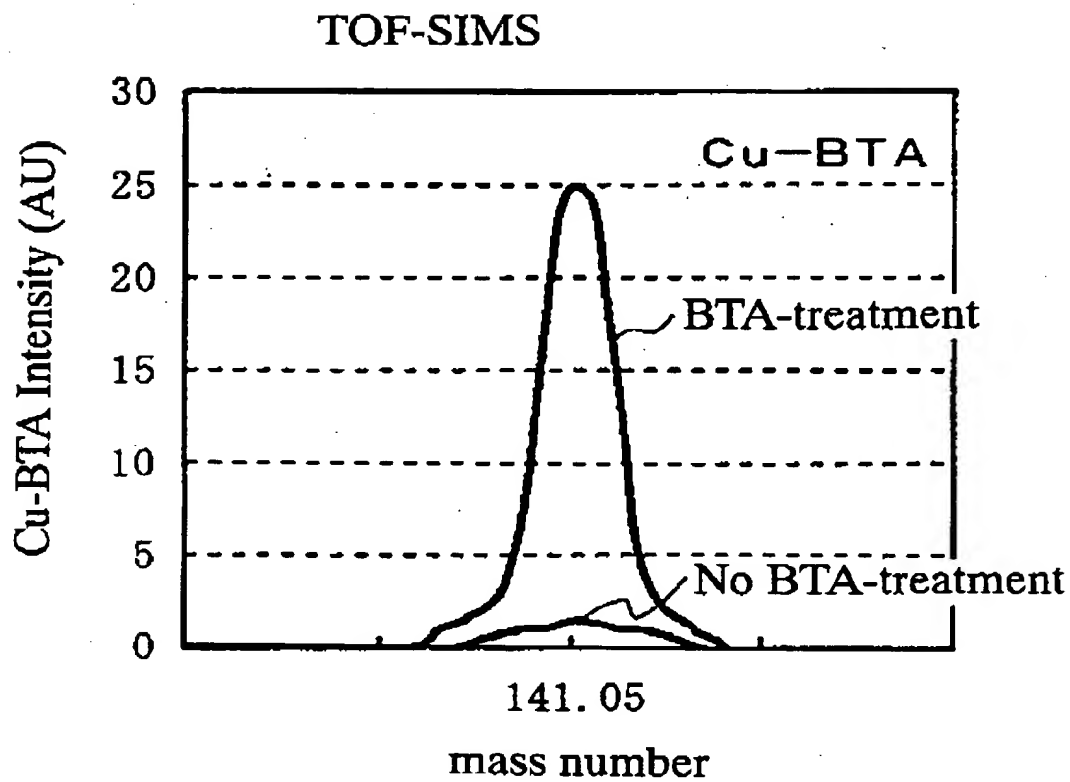
FIG. 4



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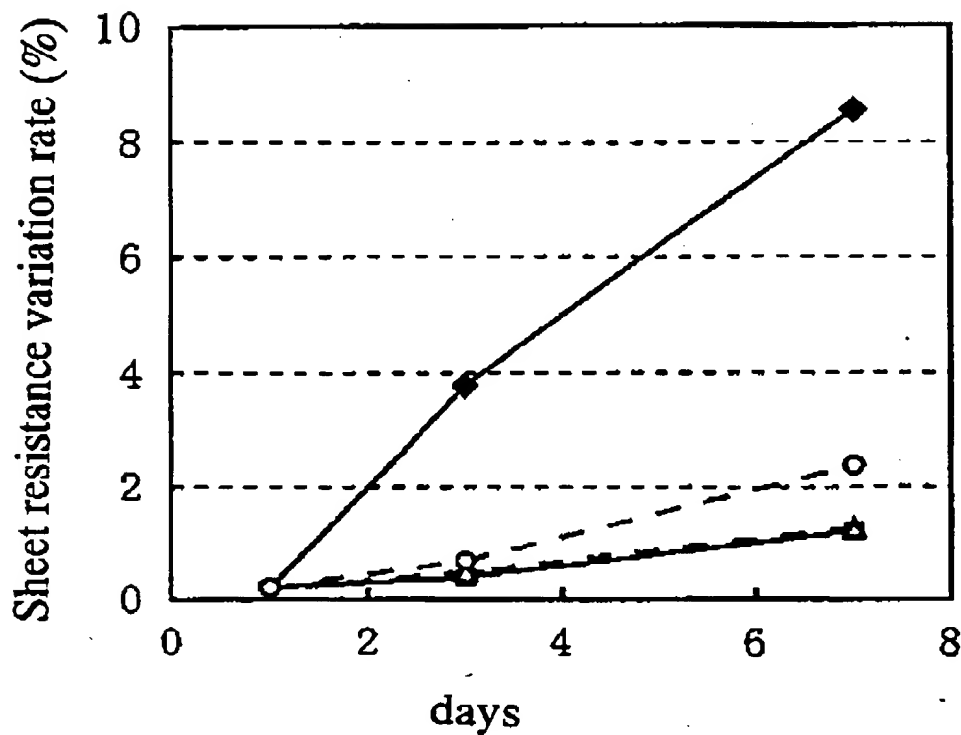
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FIG. 5



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FIG. 6



◆: the semiconductor wafer free from the benzotriazole treatment

■: the semiconductor wafer treated with the 0.1%-benzotriazole solution

△: the semiconductor wafer treated with the 1%-benzotriazole solution

○: the semiconductor wafer treated with the 1%-gallic acid solution